



1201.64722

PATENT APPLICATION

#16/C  
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6/1/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Li et al. )  
Serial No.: 09/662,682 )  
Filed: September 15, 2000 )  
For: METAL-ASSISTED CHEMICAL )  
ETCH POROUS SILICON )  
FORMATION METHOD )  
Art Unit: 1765 )  
Examiner: Vinh, Lan )

*I hereby certify that this paper is being deposited with the United States Postal Service as FIRST-CLASS mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this date.*

May 23, 2003

Date  
F-CLASS. WCM  
Appr. February 20, 1998

Ans B. R  
Registration No. 43,874

Attorney for Applicant

AMENDMENT D

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed December 26, 2002, please  
amend the above-identified application as follows:

RECEIVED  
MAY 29 2003  
TC 1700